

amount of \$110.00 for payment of the extension fee is enclosed. Please charge any additional fee required for the extension, and credit any overpayment to Deposit Account 06-1205.

Please amend the above-identified application as follows:

IN THE SPECIFICATION

Please substitute the following paragraph starting at page 36, line 15 and ending at page 36, line 19. A marked up version showing the changes made thereto is attached.

The film forming rate of the silicon nitride film was as large as 500 nm/min, and the film proved to be excellent in quality, showing a refractive index of 2.2 and having satisfactory adhesion and durability. Also it showed a density of 2.9 g/cm³, denser than in a case without the filling with the second dielectric material 704.

IN THE CLAIMS

Please amend claims 68, 78, and 110 as follows. A marked up version showing the changes made thereto, is attached.

68. (Twice Amended) A microwave plasma processing apparatus comprising:

a plasma generation chamber provided with a first dielectric material;